

ICMAP 2018

The 7th International Conference on Microelectronics and Plasma Technology

July 24-28, 2018 / Songdo ConvensiA, Incheon, Korea

Dr. Alok Ranjan

Tokyo Electron, USA



Alok Ranjan is Director & Senior Member of Technical Staff at Tokyo Electron Miyagi Ltd, Tokyo Electron's Etch Business Unit and TEL Technology Center America, LLC. He is responsible for global programs geared towards advanced plasma etch process and chamber development for current through to 3 nm technologies in logic, memory and patterning in general. He also chairs the steering committee that directs etch concept and feasibility development. A recent focus is the implementation of atomic layer etching in critical applications and "etch aware" computational patterning. He holds a BS in Chemical Engineering from Indian Institute of Technology and PhD in Chemical Engineering at the University of Houston, USA. There, his work contributed to the development of the first ballistic electron beam based plasma etchers, now in wide commercial use. Prior to joining Tokyo Electron, Dr. Ranjan held technology leadership roles at Intel and Applied Materials. In both positions, he deployed new process and chamber technologies for leading-node pilot line development. Dr. Ranjan serves on numerous industry committees including the AVS Program Committee and ALE workshop committee. He has published over 100 articles and conference papers and has over 100 patents filed or pending related to advanced semiconductor device manufacturing technology.